### **VE320 – Summer 2021**

#### **Introduction to Semiconductor Devices**

Instructor: Yaping Dan (但亚平) yaping.dan@sjtu.edu.cn

Chapter 11 Metal-Oxide-Semiconductor Field Effect Transistors: More Concepts

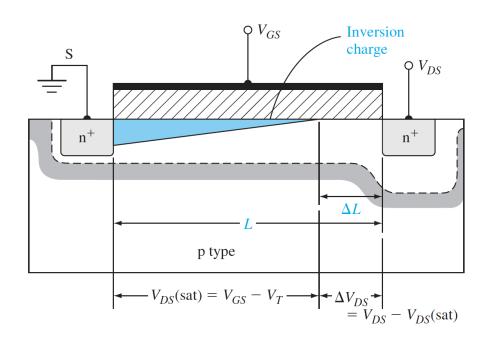
### Outline

#### Nonideal Effects:

### 11.1 Channel length modulation

- 11.3 Subthreshold conduction
- 11.4 Velocity Saturation
- 11.5 Short Channel Effect

# 11.1 Channel length modulation



$$I'_{D} = \frac{k'_{n}}{2} \cdot \frac{W}{L} \cdot \left[ (V_{GS} - V_{T})^{2} (1 + \lambda V_{DS}) \right]$$

# 11.1 Channel length modulation

$$I_{D} = \begin{cases} 0 & V_{GS} - V_{T} < 0\\ \frac{1}{2} \mu_{n} C_{ox} \frac{W}{L} (V_{GS} - V_{T})^{2} & 0 \leq V_{GS} - V_{T} < V_{DS}\\ \mu_{n} C_{ox} \frac{W}{L} [(V_{GS} - V_{T}) V_{DS} - \frac{1}{2} V_{DS}^{2}] & V_{GS} - V_{T} \geq V_{DS} \end{cases}$$



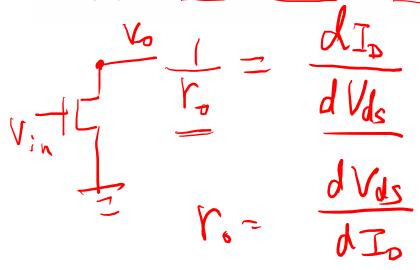
$$I_{D} = \begin{cases} 0 & V_{GS} - V_{T} < 0\\ \frac{1}{2} \mu_{n} C_{ox} \frac{W}{L} (V_{GS} - V_{T})^{2} (1 + \lambda V_{DS}) & 0 \le V_{GS} - V_{T} < V_{DS}\\ \mu_{n} C_{ox} \frac{W}{L} [(V_{GS} - V_{T}) V_{DS} - \frac{1}{2} V_{DS}^{2}] & V_{GS} - V_{T} \ge V_{DS} \end{cases}$$



# Check your understanding

#### Problem Example 1

Consider an n-channel silicon MOSFET. The parameters are  $k'_n = 75 \mu \text{A/V}^2$ , W/L = 10, and  $V_T = 0.35 \text{ V}$ . The applied drain-to-source voltage is  $V_{DS} = 1.5 \text{ V}$ . (a) For  $V_{GS} = 0.8 \text{ V}$ , find (i) the ideal drain current, (ii) the drain current if  $\lambda = 0.02 \text{ V}^{-1}$ , and (iii) the output resistance for  $\lambda = 0.02 \text{ V}^{-1}$ . (b) Repeat part (a) for  $V_{GS} = 1.25 \text{ V}$ .



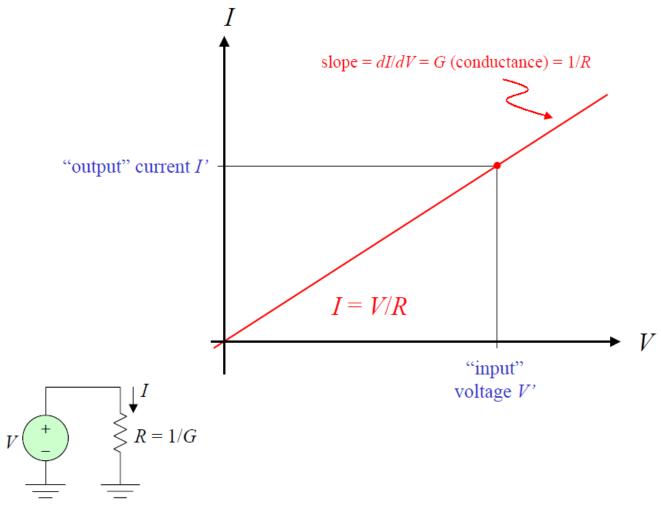
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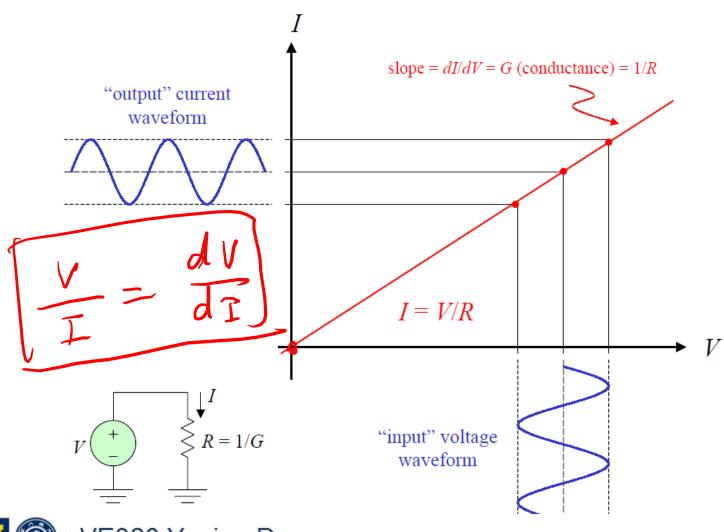
#### Nonideal Effects:

### 11.1 Channel length modulation

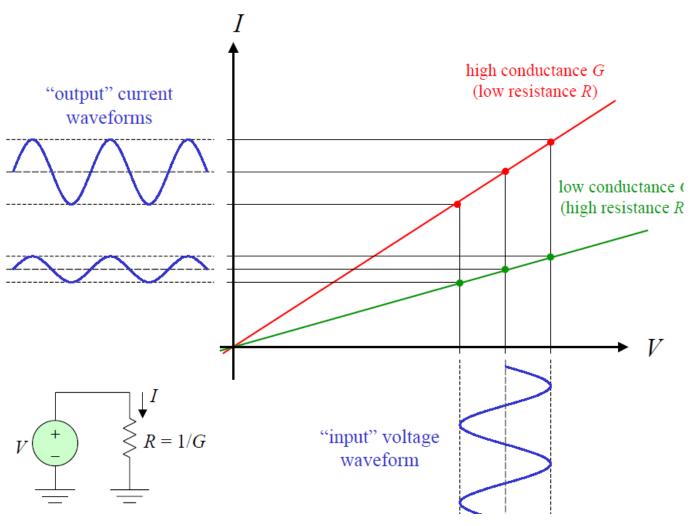
- 11.3 Subthreshold conduction
- 11.4 Velocity Saturation
- 11.5 Short Channel Effect





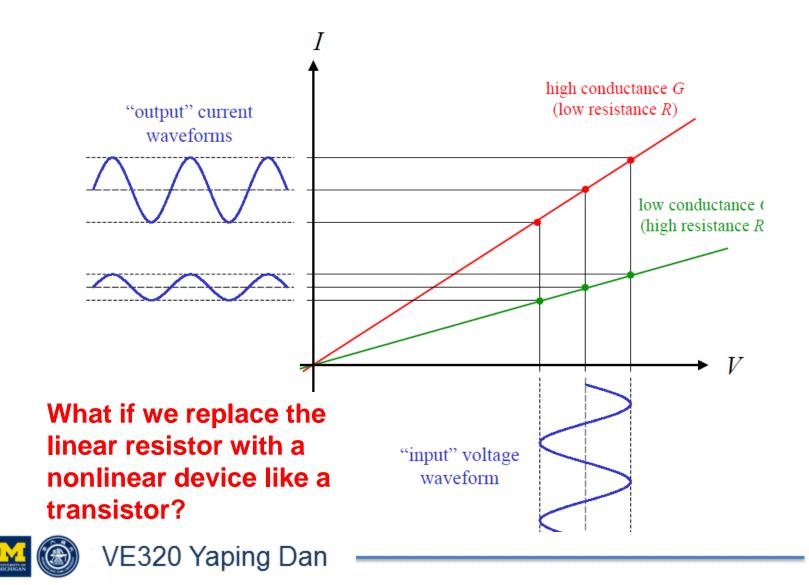


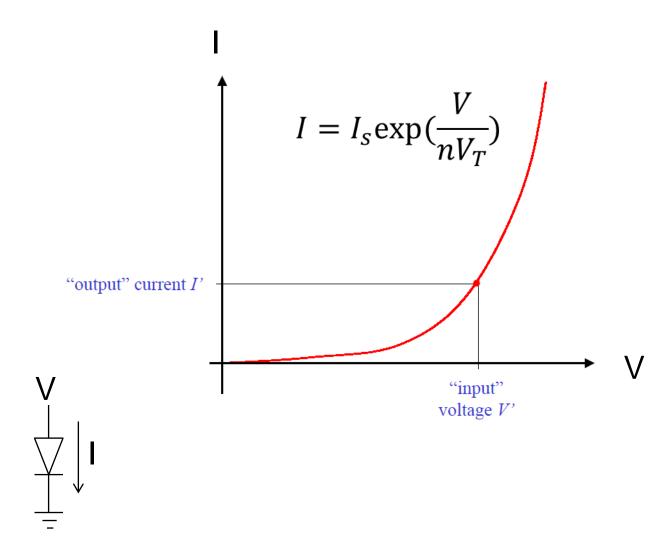


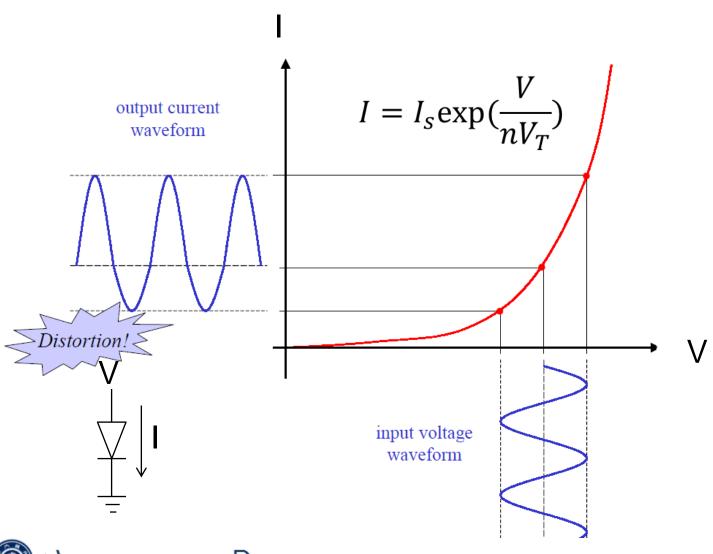






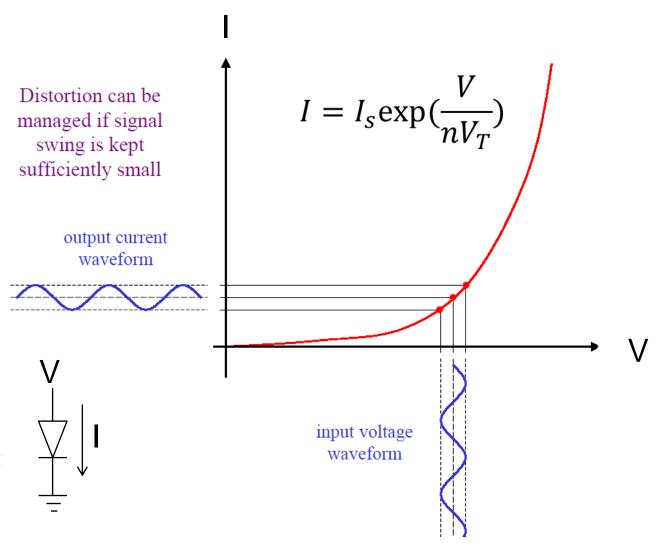




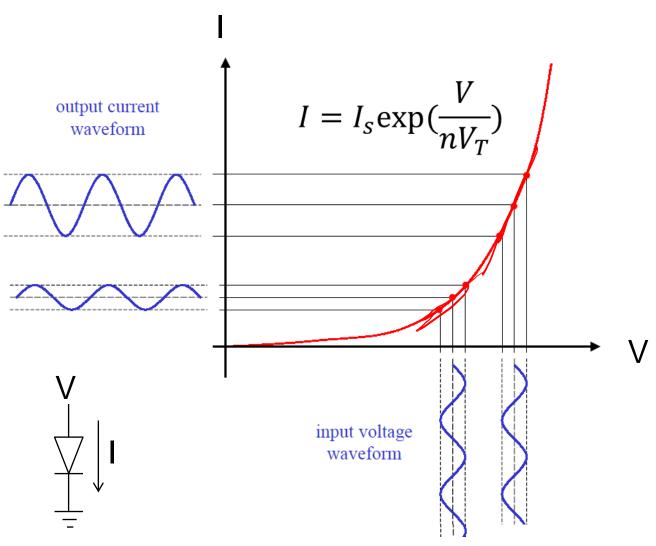






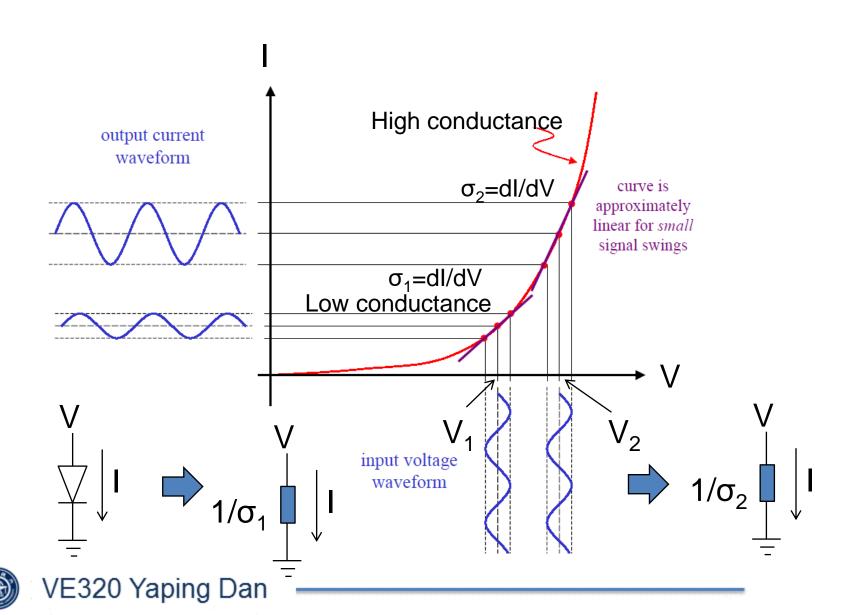


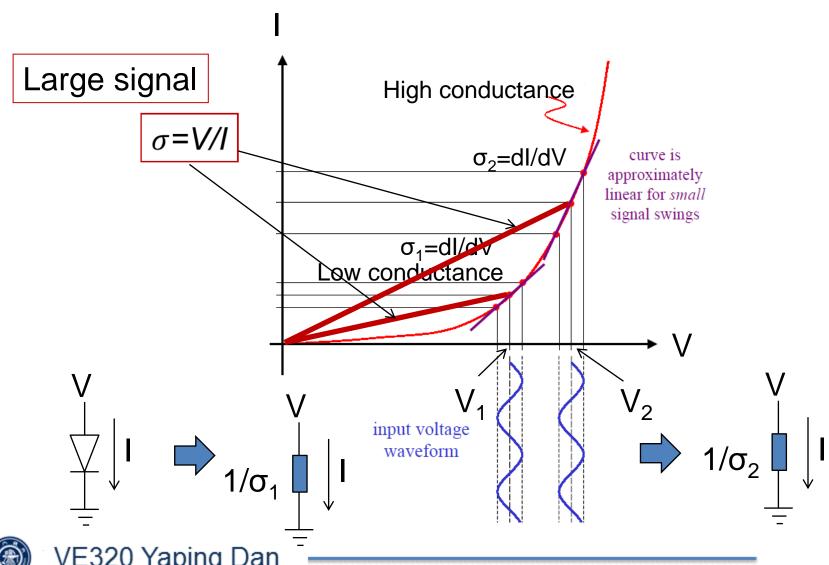






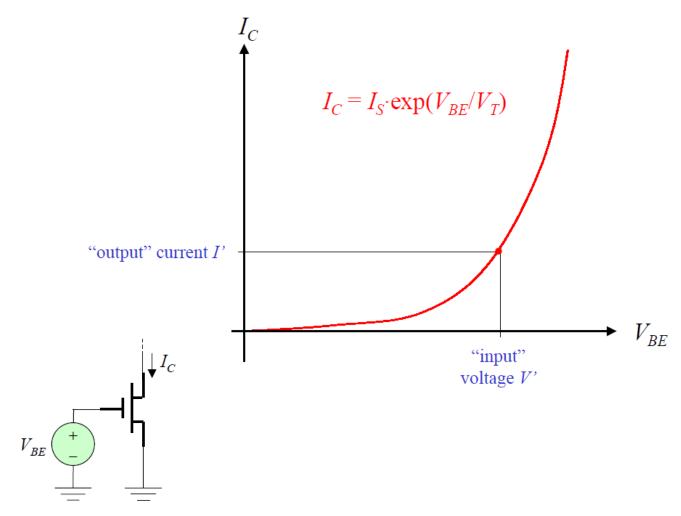


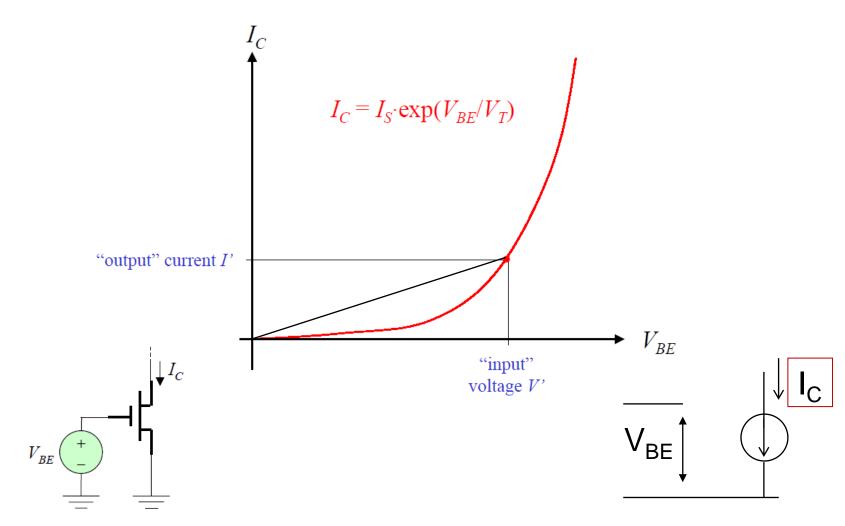




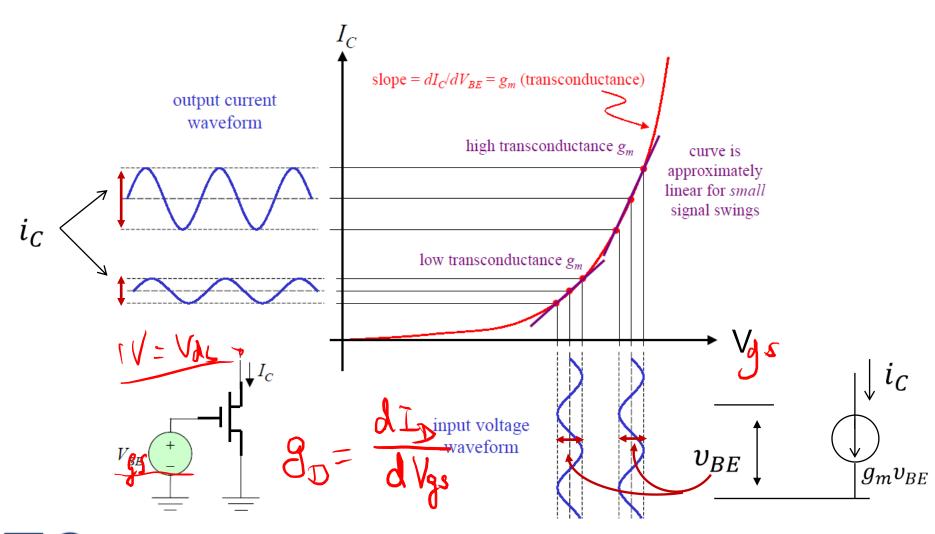
















$$I_{d} = \begin{cases} 0 & V_{gs} - V_{T} < 0 \\ \frac{1}{2}k_{n}(V_{gs} - V_{T})^{2}(1 + \lambda V_{ds}) & 0 \leq V_{gs} - V_{T} < V_{ds} \\ k_{n}[(V_{gs} - V_{T})V_{ds} - \frac{1}{2}V_{ds}^{2}] & V_{gs} - V_{T} \geq V_{ds} \end{cases}$$

$$\text{conductance} \quad \mathcal{G}_{D} = \frac{d \mathcal{I}_{D}}{d V_{ds}} = \begin{cases} \frac{1}{2}k_{n}(V_{gs} - V_{T}) & \lambda V_{ds} \\ k_{n}(V_{gs} - V_{T}) & \lambda V_{ds} \end{cases}$$

$$\text{trans conductance} \quad \mathcal{G}_{m} = \frac{d \mathcal{I}_{D}}{d V_{ds}} = \begin{cases} k_{n}(V_{gs} - V_{T}) & \lambda V_{ds} \\ k_{n}(V_{gs} - V_{T}) & \lambda V_{ds} \end{cases}$$

#### Transconductance

$$I_{d} = \begin{cases} 0 & V_{gs} - V_{T} < 0\\ \frac{1}{2}k_{n}(V_{gs} - V_{T})^{2}(1 + \lambda V_{ds}) & 0 \le V_{gs} - V_{T} < V_{ds}\\ k_{n}[(V_{gs} - V_{T})V_{ds} - \frac{1}{2}V_{ds}^{2}] & V_{gs} - V_{T} \ge V_{ds} \end{cases}$$

### Output Impedance

$$I_{d} = \begin{cases} 0 & V_{gs} - V_{T} < 0\\ \frac{1}{2}k_{n}(V_{gs} - V_{T})^{2}(1 + \lambda V_{ds}) & 0 \le V_{gs} - V_{T} < V_{ds}\\ k_{n}[(V_{gs} - V_{T})V_{ds} - \frac{1}{2}V_{ds}^{2}] & V_{gs} - V_{T} \ge V_{ds} \end{cases}$$

# How the knowledge used by engineers and scientists

# Diameter-Dependent Electron Mobility of InAs Nanowires

Alexandra C. Ford, †,‡,§,|| Johnny C. Ho,†,‡,§,|| Yu-Lun Chueh,†,‡,§,|| Yu-Chih Tseng,‡ Zhiyong Fan,‡,§,|| Jing Guo, Jeffrey Bokor,‡,§ and Ali Javey\*,‡,§,||

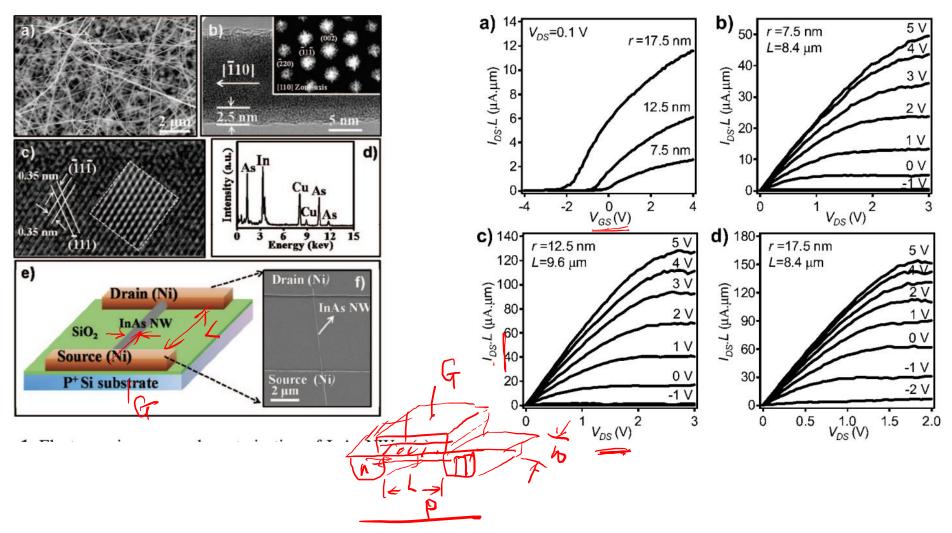
Department of Electrical Engineering and Computer Sciences, University of California at Berkeley, Berkeley, California 94720, Materials Sciences Division, Lawrence Berkeley National Laboratory, Berkeley, California 94720, Berkeley Sensor and Actuator Center, University of California at Berkeley, Berkeley, California 94720, and Department of Electrical and Computer Engineering, University of Florida, Gainesville, Florida 32611

NANO LETTERS

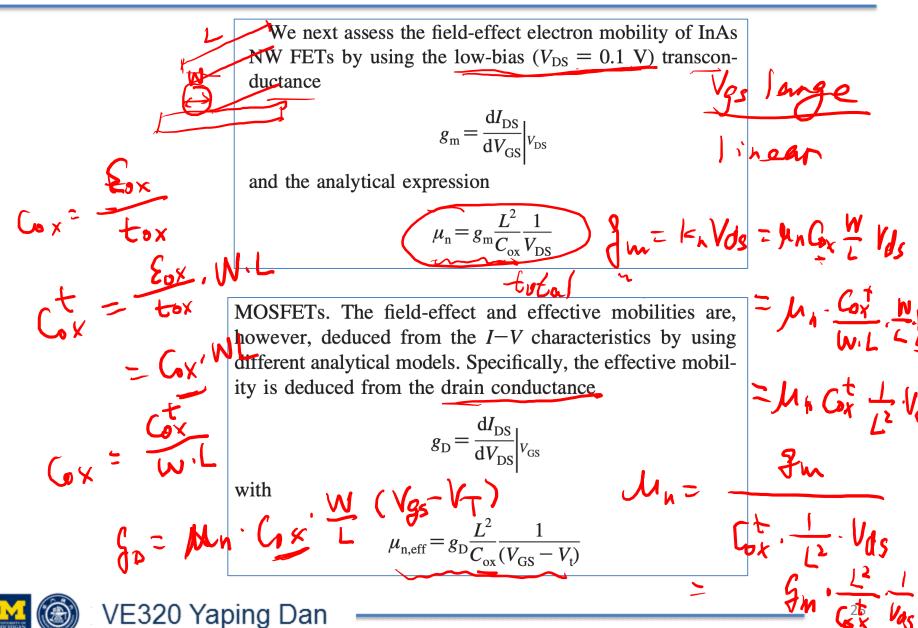
2009 Vol. 9, No. 1 360-365



# How the knowledge used by engineers and scientists



# How the knowledge used by engineers and scientists



# Check your understanding

Problem example 2

The transconductance of an n-channel MOSFET is found to be  $g_m = \partial I_D/\partial V_{GS} = 1.25$  mA/V when measured at  $V_{DS} = 50$  mV. The threshold voltage is  $V_T = 0.3$  V. (a) Determine the conductance parameter  $K_n$ . (b) What is the current at  $V_{GS} = 0.8$  V and  $V_{DS} = 50$  mV? (c) Determine the current at  $V_{GS} = 0.8$  V and  $V_{DS} = 1.5$  V.

# Outline

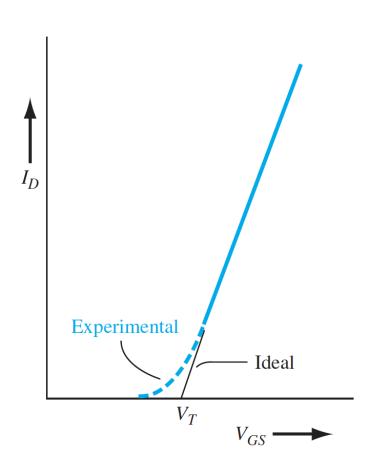
#### Nonideal Effects:

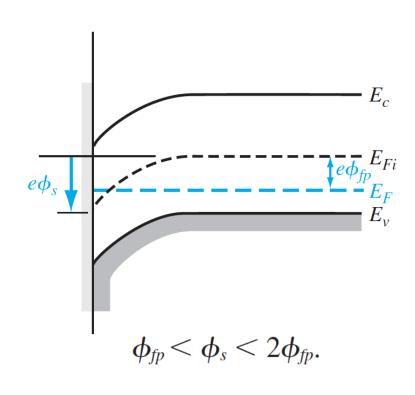
### 11.1 Channel length modulation

- 11.3 Subthreshold conduction
- 11.4 Velocity Saturation
- 11.5 Short Channel Effect

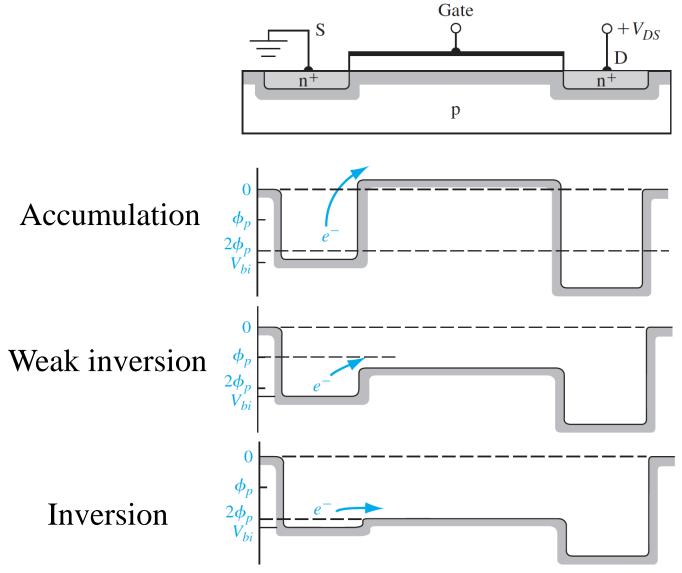
# 11.3 Subthreshold conduction







# 11.3 Subthreshold conduction

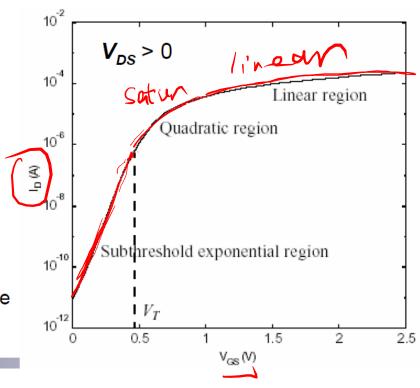


# **Subthreshold Conduction (Leakage Current)**

- The transition from the ON state to the OFF state is gradual. This can be seen more clearly when  $I_D$  is plotted on a logarithmic scale:
- In the subthreshold  $(V_{GS} < V_{\tau})$  region,

$$I_D \propto \exp\left(\frac{qV_{GS}}{nkT}\right)$$

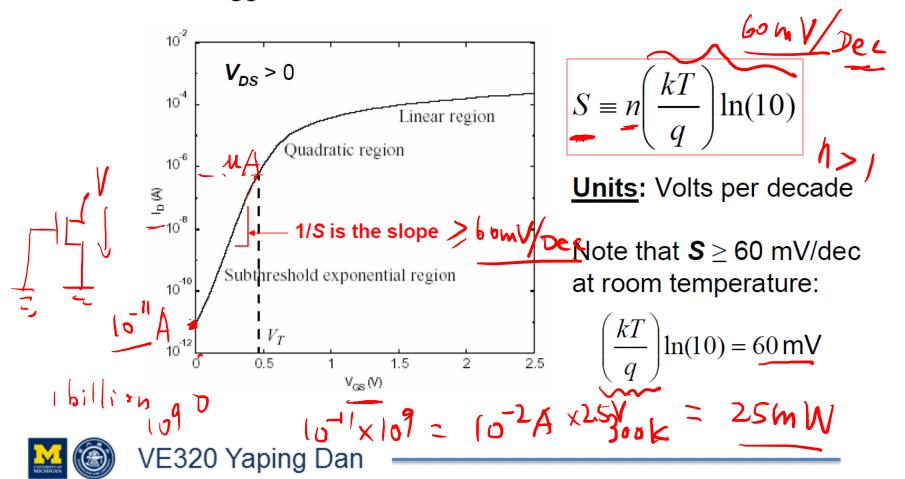
Cy This is essentially the channelsource pn junction current. (Some electrons diffuse from the source into the channel, if this pn junction is forward biased.)



# 11.3 Subthreshold conduction

# Slope Factor (or Subthreshold Swing) S

• S is defined to be the inverse slope of the log ( $I_D$ ) vs.  $V_{GS}$  characteristic in the subthreshold region:



### 11.3 Subthreshold conduction

# $V_T$ Design Trade-Off

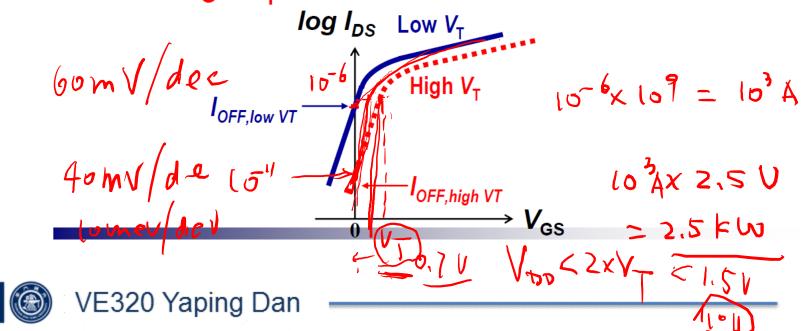
(Important consideration for digital-circuit applications)

■ Low V<sub>T</sub> is desirable for high ON current

$$I_{DSAT} \propto (V_{DD} - V_T)^{\eta}$$
 1 <  $\eta$  < 2

where  $V_{DD}$  is the power-supply voltage

...but high  $V_T$  is needed for low OFF current



# Check your understanding

#### Problem example 3

Assume that the subthreshold current of a MOSFET is given by

$$I_D = 10^{-15} \exp\left(\frac{V_{GS}}{(2.1)V_t}\right)$$

over the range  $0 \le V_{GS} \le 1$  volt and where the factor 2.1 takes into account the effect of interface states. Assume that 106 identical transistors on a chip are all biased at the same  $V_{GS}$  and at  $V_{DD} = 5$  V. (a) Calculate the total current that must be supplied to the chip at  $V_{GS} = 0.5, 0.7,$  and 0.9 V. (b) Calculate the total power dissipated in the chip for the same  $V_{GS}$  values.

sipated in the chip for the same 
$$V_{GS}$$
 values.

$$V_{GS} = 0.5V$$

$$I_D^{\dagger} = 10^6 I_D = 10^6 \times 10^{-15} \text{ exp} \left( \frac{0.5}{2.11 \times 6.0259} \right) = 9.8 \times 10^{-6} \text{ A}$$

$$V_{GS} = 0.7V \qquad I_P^{\dagger} = 3.88 \times (0^{-4} \text{A}) \qquad \square = 19 \text{ mW}$$

$$V_{GS} = 0.9V \qquad I_P^{\dagger} = 1.54 \times 10^{-2} \text{A} \qquad \square = 3.5 \times 10^{-4} \text{A}$$





# Outline

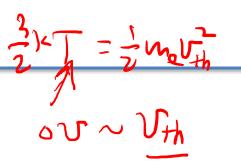
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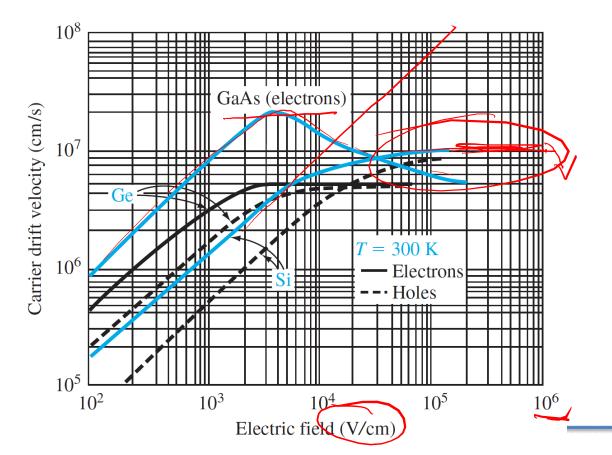


$$v_d \rightarrow v_{th}$$





- Electric field is heating up electrons
- Electrons transfer energy to lattice to reach thermal equilibrium



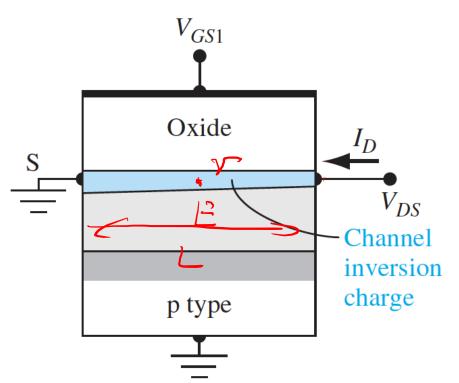
$$v_n = \frac{v_s}{\left[1 + \left(\frac{\mathbf{E}_{on}}{\mathbf{E}}\right)^2\right]^{1/2}}$$

$$v_p = \frac{v_s}{\left[1 + \left(\frac{E_{op}}{E}\right)^2\right]^{1/2}}$$

Probably a typo in textbook

$$v_d \rightarrow v_{th}$$

- Electric field is heating up electrons
- Electrons transfer energy to lattice to reach thermal equilibrium



$$E_{DS} = \frac{V_{DS}}{L}$$

As the transistor size scales down, the electric field intensity E increases.

$$E_{on} = \frac{V_{DSAT}}{L}$$

$$v_d \rightarrow v_{th}$$

As the transistor size scales down, the electric field intensity E increases.

- Electric field is heating up electrons
- Electrons transfer energy to lattice to reach thermal equilibrium

$$I_{DSAT} = \mu_n C_{ox} \frac{W}{L} \left( V_{GS} - VT - \frac{1}{2} V_{DS} \right) V_{DS}$$

$$= C_{ox} W \left( V_{GS} - VT - \frac{1}{2} V_{DSAT} \right) \left( \frac{DSAT}{L} \right) \mu_n$$

$$I_{DSAT} = WC_{ox} \left[ V_{GS} - V_T - \frac{V_{DSAT}}{2} \right] v_{sat}$$

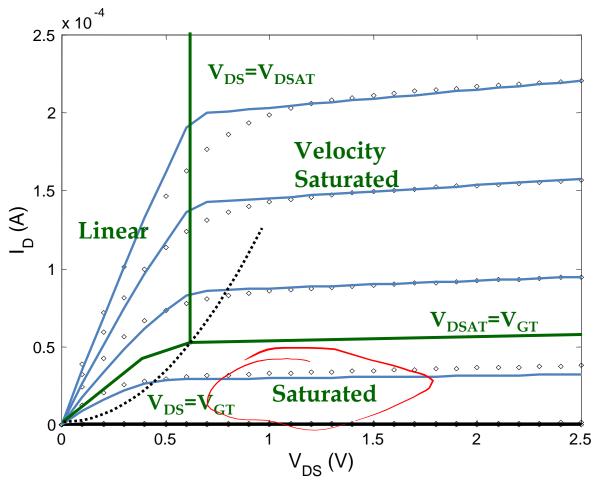
$$\text{where } V_{DSAT} = \frac{L}{\mu_n} v_{sat}$$

### Unified model

$$I_D = 0 \text{ for } V_{GT} \leq 0$$

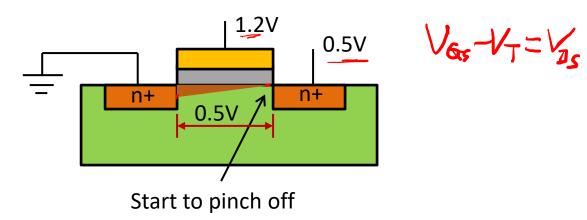
$$I_D = k' \frac{W}{L} \left( V_{GT} V_{min} - \frac{V_{min}^2}{2} \right) \qquad \text{for } V_{GT} \geq 0$$
with  $V_{min} = \min(V_{GT}, V_{DS}, V_{DSAT}),$ 

$$V_{GT} = V_{GS} - V_{T},$$
and  $V_T = V_{T0} + \gamma(\sqrt{|-2\phi_F|} + V_{SB}| - \sqrt{|-2\phi_F|})$ 

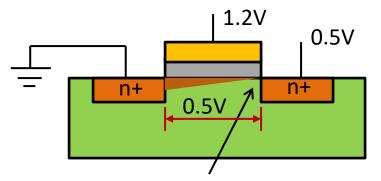




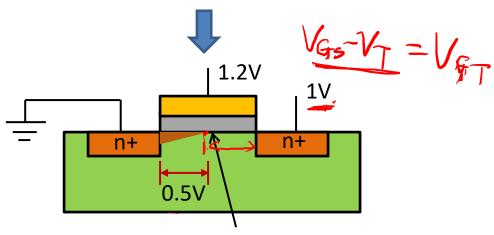
$$V_T = 0.7 \ V_{gs} = 1.2 \ V, \ V_{sat} = 1 \ V$$



$$V_T = 0.7$$
,  $V_{gs} = 1.2 \text{ V}$ ,  $V_{sat} = 10 \text{ V}$ 



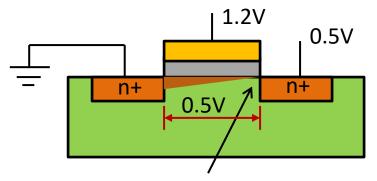
Start to pinch off



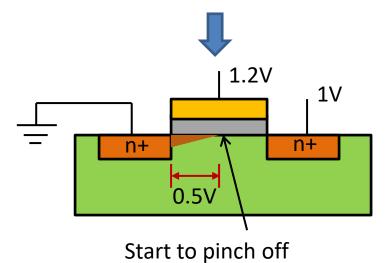
Start to pinch off

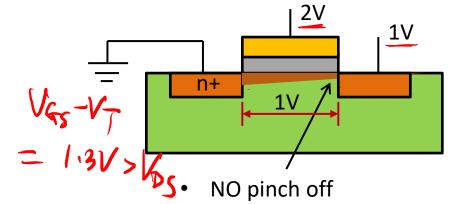


$$V_T = 0.7$$
,  $V_{gs} = 1.2 \text{ V}$ ,  $V_{sat} = 1 \text{ V}$ 



Start to pinch off

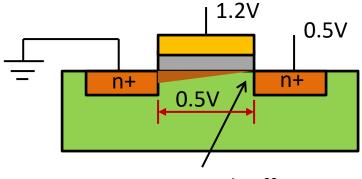




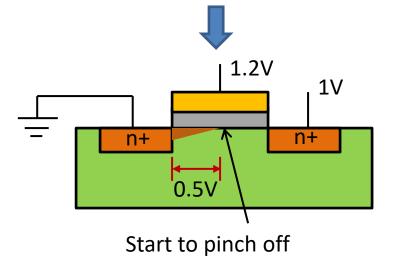
Velocity saturation starts

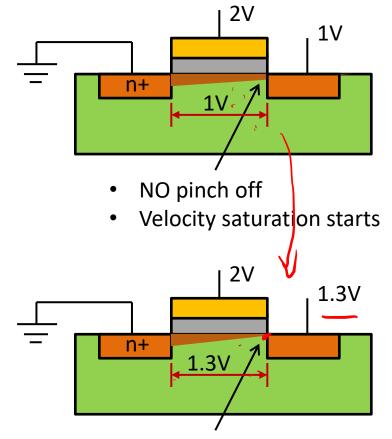


$$V_T = 0.7$$
,  $V_{gs} = 1.2 \text{ V}$ ,  $V_{sat} = 1 \text{ V}$ 



Start to pinch off





- Starts to pinch off
- Velocity saturation



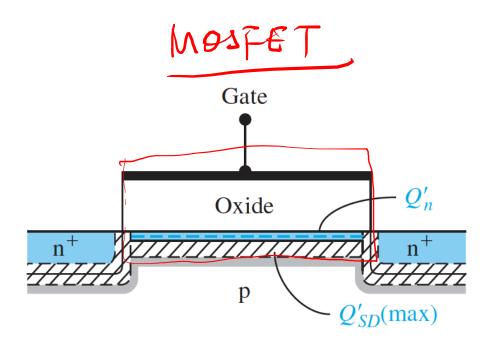
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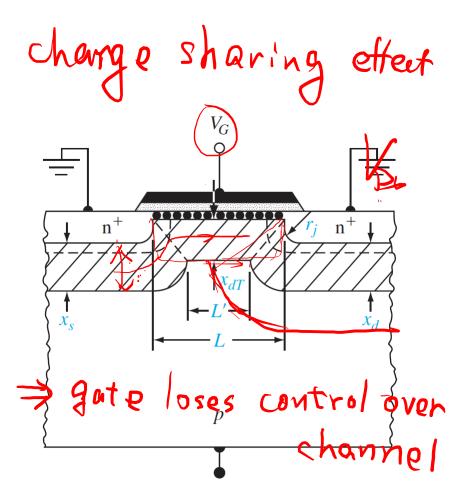
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### 11.5 Short Channel Effect

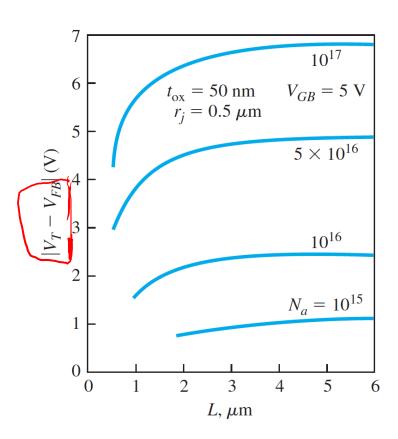


A long channel device



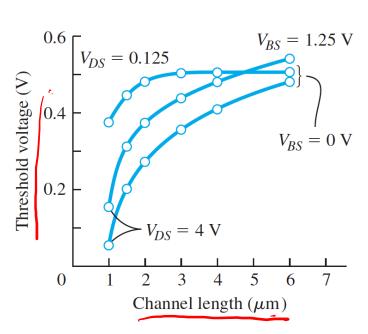
A short channel device

# 11.5 Short Channel Effect



**Figure 11.16** | Threshold voltage versus channel length for various substrate dopings. (*From Yau* [26].)



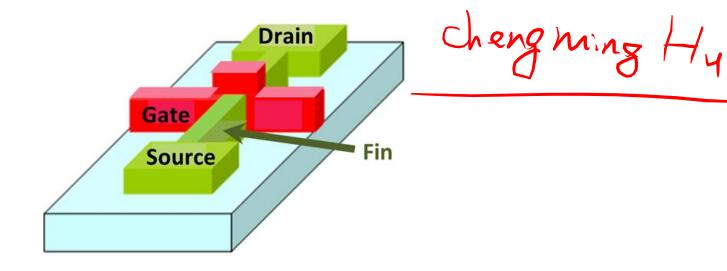


**Figure 11.17** | Threshold voltage versus channel length for two values of drain-to-source and body-to-source voltage. (*From Yang [25].*)



VE320 Yaping Dan

# 11.5 Short Channel Effect



Fin Gate to suppress short channel effect